

IN THE ABSTRACT:

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--A substrate processing system has a first processing device which processes a substrate with a first process in a first gas atmosphere within a process chamber and a transfer device that transfers a substrate in a second gas atmosphere within a clean booth, the transfer device transferring a substrate which has been processed with a second process by a second processing device or a substrate which is to be processed by that second processing device. A load-lock chamber has a substrate transfer path between the first processing device and the transfer device and there is a gas supply device which supplies the first gas from the process chamber to the load-lock chamber when the substrate is transferred between the load-lock chamber and a first processing device, and supplies the second gas from the clean booth to the load-lock chamber when the substrate is transferred between the load-lock chamber and the transfer device. This invention relates to a processing apparatus for processing a sample such as a substrate. The apparatus includes a process chamber having an exposure apparatus for transferring a pattern onto a substrate as a sample in a predetermined atmosphere, a load-lock chamber connected to the process chamber, a transfer mechanism for transferring the substrate between the load-lock chamber and a coater-developer, a clean booth which covers the transfer path of the transfer mechanism, and a transfer atmosphere forming mechanism for flowing a clean gas in the clean booth.